

CLAIMS

1. A susceptor for a thermal processing chamber comprising:
 - an outer rim surrounding and coupled to an inner dish, the outer rim having an inner edge and an outer edge; and
 - one or more elevated structures relative to an upper surface of the inner dish, the one or more elevated structures to reduce a contacting surface area between the susceptor and a substrate to be supported by the susceptor, wherein at least one of the elevated structures is coupled to the inner dish at a location proximate the inner edge of the outer rim, wherein the one or more elevated structures comprises an angled surface extending radially inward from the inner edge of the outer rim to a depression, wherein an upper surface of the depression is located below the upper surface of the inner dish and the upper surface of the depression couples the angled surface to the upper surface of the inner dish, wherein the angled surface is angled between about four degrees and about twenty degrees relative to the upper surface of the inner dish.